

6/8inch Poly-Si Etcher

Model: SA-NMC508SES

SA-NMC508SES is a mature 6/8-inch poly-Si etch equipment for mass production. It serves logic, BCD, Si/SiC power, MEMS and TFT chips, supporting Poly gate, STI, CT Si and other core processes. Adopting dual-zone plasma, gas injection and ceramic ESC designs, it delivers outstanding process uniformity and extended component lifespan. Most mainstream manufacturing processes have been verified in volume production with stable performance and competitive cost advantages.



Feature

- Good process uniformity
- Comparable
- 300mm tech
- Longer Lifetime
- More symmetric flow field

Application

- Logic
- BCD
- Si/SiC Power
- MEMS
- TFT

Specifications:

Parameter	Descriptions
Wafer Size	6/8inch
Etching Materials	Si/PolySi
Processes	Poly EB/STI/Poly gate/CT Si
Coil	Dual Zone
Match Mode	L-Match
Magnetic Shield	Yes
Gas Injector	Dual Zone
FRC	Yes
Liner	Symmetric Grid
Edge Ring	CIP version
ESC	Dual Zone
ESC Materials	Ceramic
Lift Pin	Ceramic
Turbo	1600L/s
Chamber	Symmetric
W×L×H	3253×3279×2339 mm

Principle:

